Test-beam Measurements of Instrumented Sensor Planes for a Highly Compact and Granular Electromagnetic Calorimeter

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42nd International Conference on High Energy Physics, ICHEP-2024, 17 - 24 July 2024, Prague

The LUXE project at DESY, Hamburg

LUXE: Laser Und XFEL Experiment



LUXE milestones documents:

- LOI (2019) 1909.00860
- CDR (2021) EPJ ST 230, 2445 2560
- TDR (2023) 2308.00515 (EPJ ST Accepted)

LUXE Collaboration

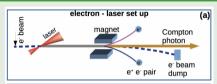


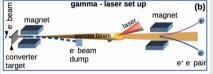
- at DESY as the host laboratory
- at Eu.XFEL 16.5 GeV electron beam
- over 20 participating institutes
- about 150 active scientists

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Physics Programme at LUXE: Study of QED in the strong field non-perturbative regime

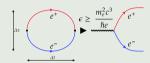
LUXE: Two modes of operation





- e-laser: using 16.5 GeV XFEL e⁻ beam
- ullet γ -laser: using bremsstrahlung γ photons
- collide them with High Power (40 or 350 TW) optical UV Laser (HPL) [phase-0 / phase-1]

non-linear and non-perturbative QED

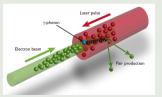


physics at and above Schwinger limit:

$${\cal E}_{cr} = rac{m_e^2 c^3}{\hbar e} = 1.3 imes 10^{18} \, {
m V/m},$$

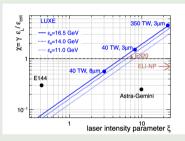
 \bullet boosted frame: $\chi = \gamma \frac{\mathcal{E}_{\mathit{HPL}}}{\mathcal{E}_{\mathit{cr}}}$

$$\textit{RMS}(\mathcal{E}_{HPL}) \sim 10^{14} \: \mathrm{V/m} \ (\times 10^4 \: \mathrm{e^- \ boost})$$



LUXE: the detectors challenge: very high rate of particles

Parameters space and e^+ rate

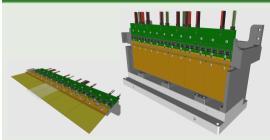


• laser intensity, dimensionless amplitude of $\mathscr E$ field): $\xi = \frac{m_e \mathscr E_L}{\omega_L \mathscr E_{ext}}$, ω_L - laser frequency



expected positron rate: 10⁻⁵ – 10⁶ per BX,
 EM showers overlap at high multiplicity

Solution for e^+ calorimetry: ECALp



- compact, high density sampling calorimeter
- ullet small Moliére radius: \sim 9 mm
- high granularity
- ullet 21 layers of 3.5 mm (1 X_0) tungsten absorber
- 1 mm gaps instrumented with active sensors

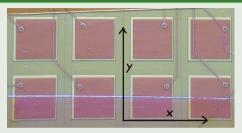
ECALp: semiconductor sensors investigated on the test-beam

Gallium Arsenide sensor:



- National Research Tomsk State University
- GaAs crystals compensated with chromium
- \bullet 4.7 \times 4.7 mm² pads, 0.3 mm gap between pads
- ullet pads are made of 0.05 μ m vanadium layer
- ullet thickness 500 $\mu \mathrm{m}$
- total wafer area: $51.9 \times 75.6 \text{ mm}^2$
- Aluminum traces in the gaps between pads
- better radiation tolerance then silicon

Silicon sensor:



- produced by Hamamatsu (CALICE design)
- ullet Si crystals: p+ on n substrate diodes
- $\bullet~5.5\times5.5~\text{mm}^2$ pads, 0.01 mm gap between pads
- few nm pads Al metalization
- \bullet thickness 500 μ m (320 μ m)
- ullet total wafer area: $89.7 imes 89.7 imes mm^2$
- external kapton fan-outs with copper traces connected to the sensor pads with conductive glue

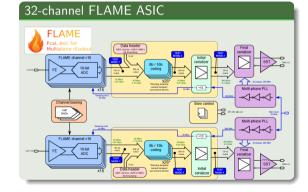
ECAL_p TB ICHEP 2024

FLAME/FLAXE front-end ASIC

- FLAME (FcaL Asic for Multiplane rEadout) is a 32-channel ASIC in CMOS 130 nm
- 10-bit ADC in each channel, two fast (5.2 Gbps) serializers and data transmitters
- FLAME has been already used in several test-beams of FCAL and LUXE-ECALp collaborations
- final DAQ version will use a new front-end ASIC FLAXE, which is based on FLAME (in progress)

FLAME ASIC specification

- Analog front-end in each channel:
 - ullet CR-RC shaping ($T_{peak}\sim 50$ ns)
 - two switched gains (high gain for MIPs, low gain for showers)
 - $C_{in} \sim 20 40 \text{ pF}$
- 10-bit ADC per channel:
 - $f_{sample} = 20 \text{ MHz}$
 - ENOB > 9.5 (effective resolution)
 - Power < 350 μ W @ 20 MHz

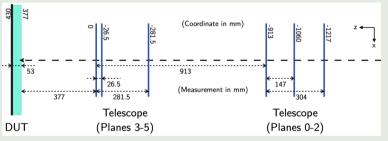


ICHEP 2024

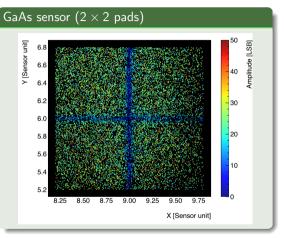
Test beam setup, DESY, Hamburg (September 2022)

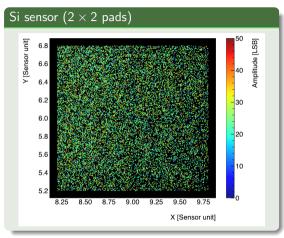
Beam telescope, scintillators and Detector Under Test (DUT)

• Electrons arrive from the right, pass the first scintillator, then six ALPIDE pixel sensors, the second scintillator, and hit the sensor, denoted as DUT (Detector under Test) \sim 35 μ m resolution of the track extrapolated from the TB telescope



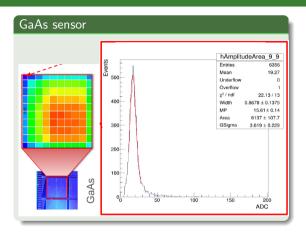
- ullet Two 16 imes 8 pad arrays of Silicon sensors and two 15 imes 10 pad arrays of GaAs sensors were tested on 5 GeV electron beam at the DESY-II facility
- investigated were homogeneity of the sensor response, edge effects and signal sharing between pads
- in addition: test of the FPGA based data on-line preprocessing (amplitude and time reconstruction)

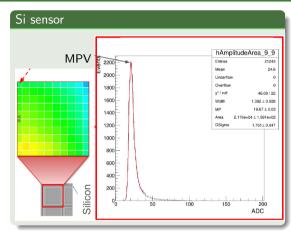




- ullet after alignment with beam telescope (\sim 35 μ m resolution on DUT XY)
- color (Z scale) indicates the size of the signal
- loss of signal for GaAs sensor in the region between pads

Sensor homogeneity study

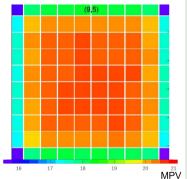




- ullet Pads were subdivided into 10 imes 10 XY sections and plotted was amplitude distribution in each section
- ullet Fits of Landau distribution convoluted with Gaussian o Most Probable Value (MPV) on next page
- color (Z scale) encodes the statistic of hits

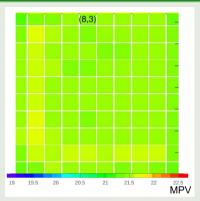
Sensor homogeneity study (cont.) : 10×10 pad subsections

GaAs sensor (single pad)



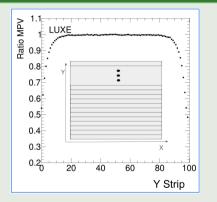
- GaAs: Drop in amplitude around edges and esp. in corners
- color (Z scale) encodes the MIP value

Si sensor (single pad)



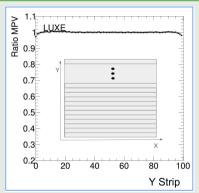
- Si: more uniform response, but...
- ... L-shaped area of a bit higher amplitude

GaAs sensor (single pad)



• GaAs Y scan: MPV drop : 50% wrt pad center

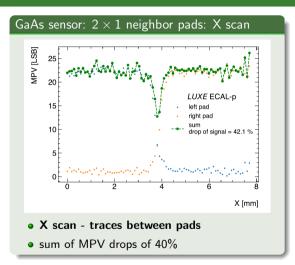
Si sensor (single pad)

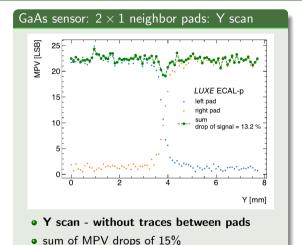


• Si Y scan: MPV drop: 2-3% wrt pad center

• Normalized to MPV of central strip. Similar response along X direction

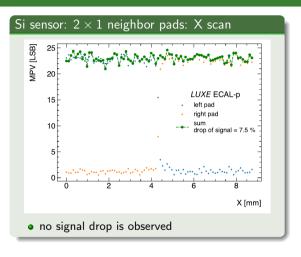
GaAs sensor: signal sharing between pads

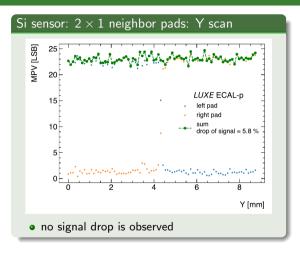




- MPV measured as a function of x and y, crossing the area between two pads
- ullet gap between GaAs pads 300 μ m

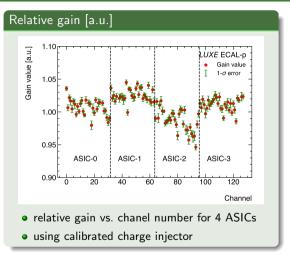
Si sensor: signal sharing between pads

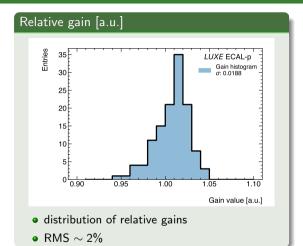




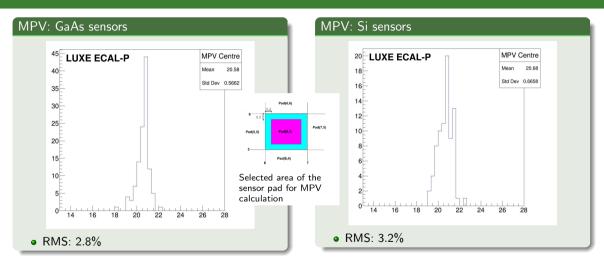
- MPV measured as a function of x and y, crossing the area between two pads
- \bullet gap between Si pads 10 μ m

Uniformity of front-end amplification





• good homogeneity of front-end preamplifiers, some dependence on ASIC fabrication (?)

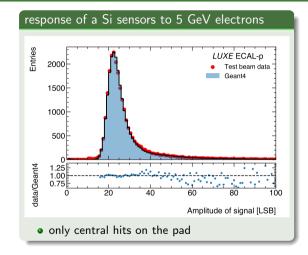


• MPV distribution after gain correction, excluding edge effect (20% margin)

Comparison with Geant4 MC simulation

response of a Si sensors to 5 GeV electrons

- ullet energy loss dE/dx [GeV] in 500 $\mu{\rm m}$ Si sensor from Geant4
- energy loss converted into number of charge carriers using 3.6 eV per electron-hole pair
- gain of the read-out chain determined from charge injection: 3.45 LSB/fC
- as a cross-check 3.46 LSB/fC was obtained fitting the gain as a free parameter



Summary

- two types of semiconductor sensors (GaAs and Si) for high density EM calorimeters were tested at 5 GeV electron beam at DESY
- energy losses for MIPs are well described by Landau distribution convoluted with Gaussian function
- homogeneity and signal sharing study were performed using hit position from the beam telescope
- for GaAs sensors edge effect are observed related to aluminum tracers and bigger gap between pads (up to 40-50% signal drop)
- for silicon sensor edge effects are barely visible
- after gain correction, in the central region of pads the homogeneity of the sensors amounts to 2.8 and
 3.2 % for the GaAs and Si sensors, respectively
- collected data are in good agreement with Geant4 based MC
- readout electronics absolute gain agrees between MC simulations and independent lab measurement (converting the energy loss into charge and using the gain of the readout chain)

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Thank You Very Much for Your Attention!

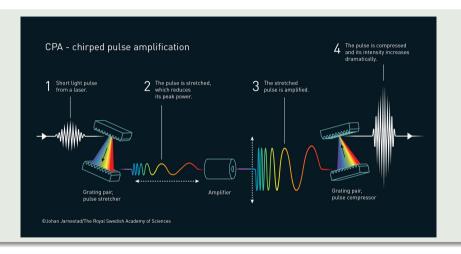
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18 / 24

BACKUP PLOTS

BACKUP PLOTS FOLLOWS...

CPA: Chirped Pulse Amplification



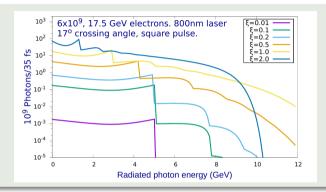
2018 Nobel Pize Donna Strickland and Gerard Mourou "for method of generating high-intensity, ultra-short optical pulses"

dimensionless intensity parameter (filed energy density) ξ^2

- $\xi^2 = 4\pi\alpha(\frac{\mathscr{E}_L}{m_e\omega_L})^2 = (\frac{m_e\mathscr{E}_L}{\omega_L\mathscr{E}_{cr}})^2$, \leftarrow "classical picture" ω_L laser frequency, ξ "dimensionless amplitude" of \mathscr{E} field
- $\xi^2 = 4\pi\alpha\lambda_L\lambda_C^2n_L$, \leftarrow "quantum picture" λ_L and λ_C - reduced laser and Compton wavelengths, $\lambda_L \sim 1~\mu{\rm m}$ $\lambda_C \sim 10^{-6}~\mu{\rm m}$ n_L - number density of laser photons

• for low and moderate $\xi \lesssim 1$ the probability of net absorption of n laser photons $\propto (\xi^2)^n \sim \alpha^n$ (consistent with perturbative QED vertex counting)

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- low laser intensity $(\xi) \to \text{KleinNishina process}$
- ξ \nearrow : increasing flux of Compton photons
- $\xi \nearrow$: shift of Compton edge with laser intensity (\rightarrow next page)
- additional structure due to multi-photon absorption

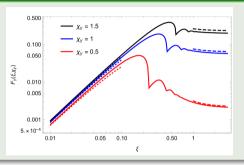
Non-linear Compton γ spectrum

$$e^- + n\gamma_L
ightarrow e^- + \gamma$$

- ullet for monochromatic, circularly polarized laser pulse: $|ec{\mathcal{E}}| = const$
- ullet in transverse plane circular motion of electron with frequency ω_L
- energy accumulated in this transverse degree of freedom can be treated as extra, effective mass of the electron
- electron transverse momentum: $P_{\perp} \sim \xi m$
- \bullet $E^2 = m^2 + P_{\perp}^2 + P_{\parallel}^2 \sim (1 + \xi^2)m^2 + P_{\parallel}^2$
- electron effective mass: $\overline{m} = m\sqrt{1+\xi^2}$
- ightarrow shift of the lowest order Compton edge (scaling as $1/\sqrt{1+\xi^2}$)
- ullet ightarrow can be used to monitor the intensity parameter ξ

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full calculation and asymptotic behavior (dotted-dashed)



- in a constant static field: $\propto \exp\left(-\pi \frac{\mathscr{E}_{cr}}{\mathscr{E}}\right)$ (Schwinger process)
- in plane wave laser (asymptotic): $\propto \exp\left(-\frac{8}{3}\frac{1}{1+\cos\theta}\frac{m_e}{\omega_I}\frac{\mathcal{E}_{cr}}{\mathcal{E}}\right)$
- \bullet good agreement for $\xi \ll 1$ and $\xi > 1$
- ullet initial growth with ξ then drop due to the Compton edge shift